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# JVSTA

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## Vacuum, Surfaces, and Films

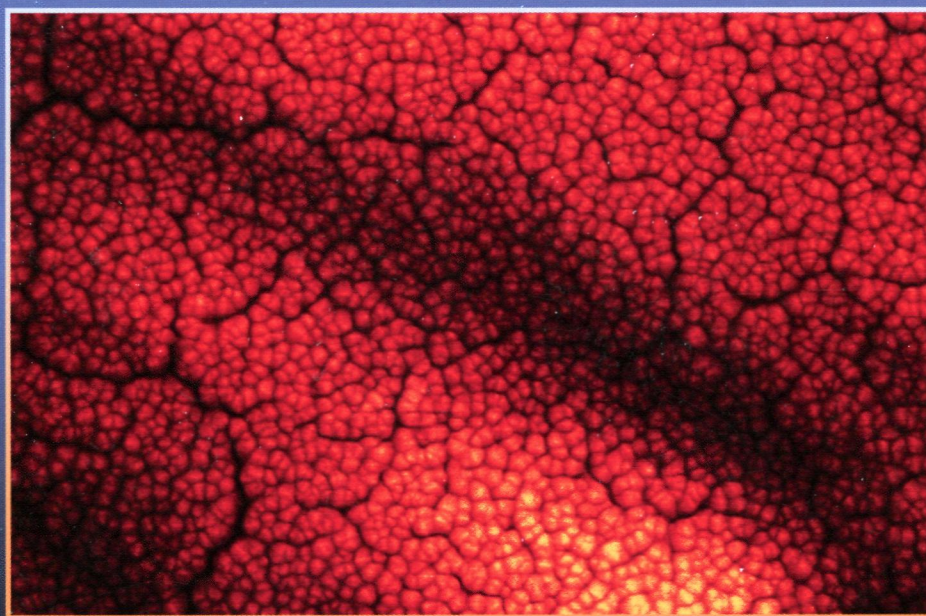


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#### Nonisostructural Complex Oxide Heteroepitaxy

-by Franklin J. Wong and Shriram Ramanathan

#### Magnetocaloric Effect in Nanoscale Thin Films and Heterostructures

-by Casey W. Miller, Dustin D. Belyea and Brian J. Kirby



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**On The Cover:** Phillip D. Swartzentruber, Thomas John Balk, and Michael P. Effgen, *JVST A* **32**(4), p. 040601-1 (2014). Cover shows the nanocrystalline grain structure of an as-deposited osmium-ruthenium alloy thin film. The film enhances thermionic emission from dispenser cathodes.